

Photoconductivity study of Ca₂Si epitaxial film on Si(111) substrate

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ARTICLE INFO

Keywords:

Ca₂Si film
Si(111) substrate
Epitaxy
Photoconductivity
Band gap nature
Temperature dependence
Electron-phonon interactions
Modelling

ABSTRACT

Semiconductor calcium semi-silicide (Ca₂Si) with a complex crystal and energy band structure is theoretically characterized by a direct fundamental transition, which is difficult to identify experimentally in Ca₂Si films due to high absorption at defect levels. The study of the temperature dependences of photoconductivity in Ca₂Si epitaxial films is one of the methods for assessing both the nature of the fundamental transition and a number of thermodynamic parameters. In this work, photoconductivity was firstly observed in an epitaxial Ca₂Si film grown on a Si(111) substrate in the temperature range from 10 K to 300 K. Based on an analysis of the parameters of three thermodynamic models, the existence of a direct fundamental transition $E_g = 1.195$ eV at 0 K was proved, and the effective phonon energy ($\langle E_{ph} \rangle$), the Einstein (Ξ) and Debye (Θ_D) temperatures, as well as the electron-phonon coupling constant, and the hole mobility were determined.

1. Introduction

Semiconductor silicides of alkaline earth metals (Ca, Mg, Ba) attract considerable attention as promising materials for thermoelectric converters [1]. Among these elements, calcium (Ca) is one of the most common elements on Earth and occupies 5th place in their total distribution [2]. Calcium silicides form six compounds with different crystal structures and compositions [3] and have a wide range of properties from semiconductor [4,5] to semimetallic from theoretical [6] and experimental points of view [7–11]. Interest in CaSi₂ with a direct gap ranging, according to *ab-initio* theoretical calculations, from 0.30 to 0.36 eV [12–14] to 1.02 eV [4] is connected mainly to its possible incorporation into existing silicon technologies and utilization in microelectronic devices [15].

Transport properties of Ca₂Si thin films, including the resistivity $\rho(T)$ and the Hall coefficient $R(T)$, were studied, and an effective mobility of about 300 cm²/Vs was estimated [15–17]. The band gap determined from the data of the *in situ* Hall temperature measurements of two-dimensional Ca₂Si layer grown on Si(111) substrate [17] was found to be equal to 1.02 eV, which is consistent with *ab-initio* calculations in the quasiparticle approach within the framework of the GW approximation [4].

From the transmission and reflection spectra of the grown samples, it was found that Ca₂Si film has a first direct interband transition at $E_{1d} = 1.095 \pm 0.15$ eV [18], strong defect adsorption lower 1.0 eV and

dispersionless refractive index $n_o \leq 3.8$. Eight Raman peaks and 6 FIR peaks were first registered and identified, which are in good agreement with the experimental study [18] and theoretical calculations [19]. Although Ca₂Si is a semiconductor compound according to first-principle theoretical calculations [4,7–9] and experimental data [18,19], carrier photogeneration in it has not been previously studied.

In this study, we report on band gap energy and temperature-dependent photoconductivity (PC) measurements of Ca₂Si epitaxial film grown on Mg₂Si/Si(111) system. The value of the band gap is determined from PC measurements and the temperature dependence of the direct gap was studied using three different models, namely the three-parameter thermodynamic model of O'Donnell and Chen [20], the Einstein model [21] and the Pässler model [22].

2. Experimental procedure

2.1. Thin film and device structure preparation

Experiments on the growth of Ca₂Si films on a substrate with (111) orientation were carried out in the ultrahigh-vacuum (UHV) chamber of the OMICRON Compact setup, the analytical and technical equipment of which was described in previous work [18]. The growth of the Ca₂Si films consisted of three stages [18]: (1) formation of a sacrificial Mg₂Si layer by reactive deposition epitaxy (RDE) at 150 °C; (2) formation of a Ca₂Si seed layer by RDE at 250 °C and (3) growth of a thick Ca₂Si film

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<https://doi.org/10.1016/j.vacuum.2022.111302>

Received 12 April 2022; Received in revised form 2 June 2022; Accepted 28 June 2022

Available online 1 July 2022

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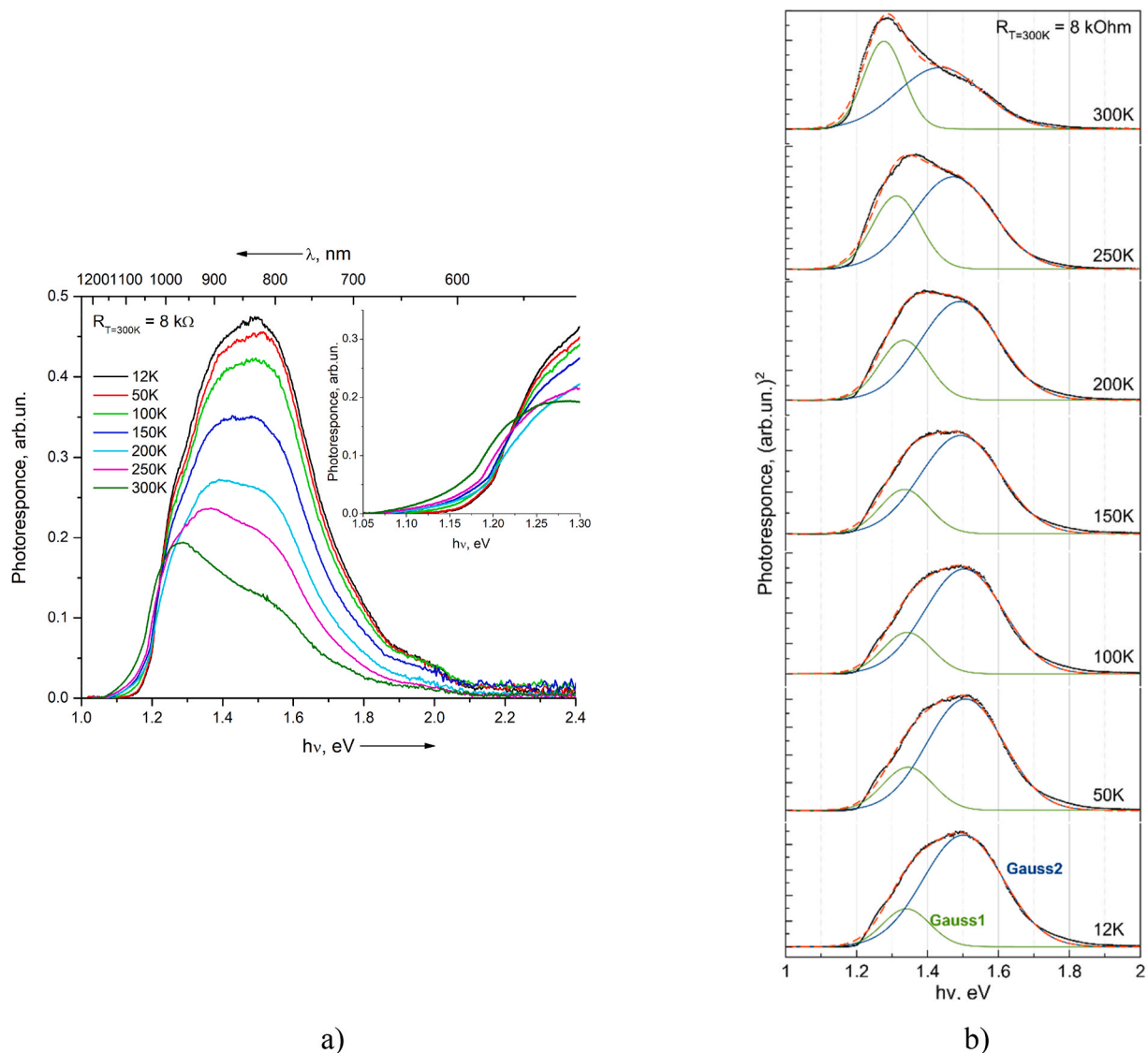


Fig. 1. a) Temperature dependence of the near-band-edge PC spectra for $\text{Ca}_2\text{Si}/\text{Si}$ system; b) Deconvolution of quadratic relation of PC for $\text{Ca}_2\text{Si}/\text{Si}$ system.

(100 nm) by molecular beam epitaxy (MBE) at 250 °C. The morphology and structure of the grown Ca_2Si films on Si(111) substrate were studied for samples **A**, **B** and **C** by AFM and XRD methods in detail in Ref. [18]. After the samples were unloaded from the UHV chamber, aluminum (Al) pads were applied to them through a contact mask and annealed in a special vacuum chamber, then the Hall cross structure was etched, and Al wires (20 μm thick) were subjected to ultrasonic welding to the contact pads in an unclosed microcircuit package. The resulting device structures were used for low-temperature measurements of the conductivity and photoconductivity of the grown films.

2.2. Photoconductivity measurements

The PC of the studied compound was measured using a custom setup consisting of a monochromator, close-circuit helium cryostat and lock-in amplifier. A halogen light source with a Tungsten filament connected to a monochromator provided discrete wavelengths in the range of 500–1200 nm (1.03–2.48 eV). Monochromatic light rays were modulated with a mechanical chopper at 12 Hz and were focused on the surface of the sample. The output photocurrent signal was collected as the voltage drop on a load resistance R which was equal to the resistance of the sample at room temperature. In the case of Ca_2Si , the load

resistance was 8 k Ω . The signal was collected and analysed by the lock-in amplifier. Temperature evolution of the PC was measured in the temperature range of 12 K–300 K. The PC spectra are calibrated by the spectral constant of the setup, which accounts for characteristic spectra of the monochromator, tungsten lamp, and slit width.

3. Results and discussion

In Fig. 1(a) temperature dependence of PC spectra is shown for $\text{Ca}_2\text{Si}/\text{Si}$ system in sample **A** grown in Ref. [18]. At every temperature, the PC spectrum is composed of two peaks, which becomes evident after deconvolution with Gauss curves (Fig. 1 b). Positions of these peaks at 12 K are 1.34 eV and 1.50 eV, however, at 300 K, both peaks shift toward lower energy positioning at 1.28 eV and 1.43 eV respectively. It is also worth noting that temperature change causes energy transfer between these two states. The intensity of respective peaks changes alternately at low and high temperatures. A comparison of the PC spectra of the $\text{Ca}_2\text{Si}/\text{Si}$ system and a pure Si substrate (not shown) over the entire temperature range, showed that the PC signal of the Si substrate is approximately one order of magnitude weaker than that of $\text{Ca}_2\text{Si}/\text{Si}$ system in the energy range of 1.2–1.8 eV. Change in the spectral composition at 1.2–1.4 eV suggests that predominant contribution to the

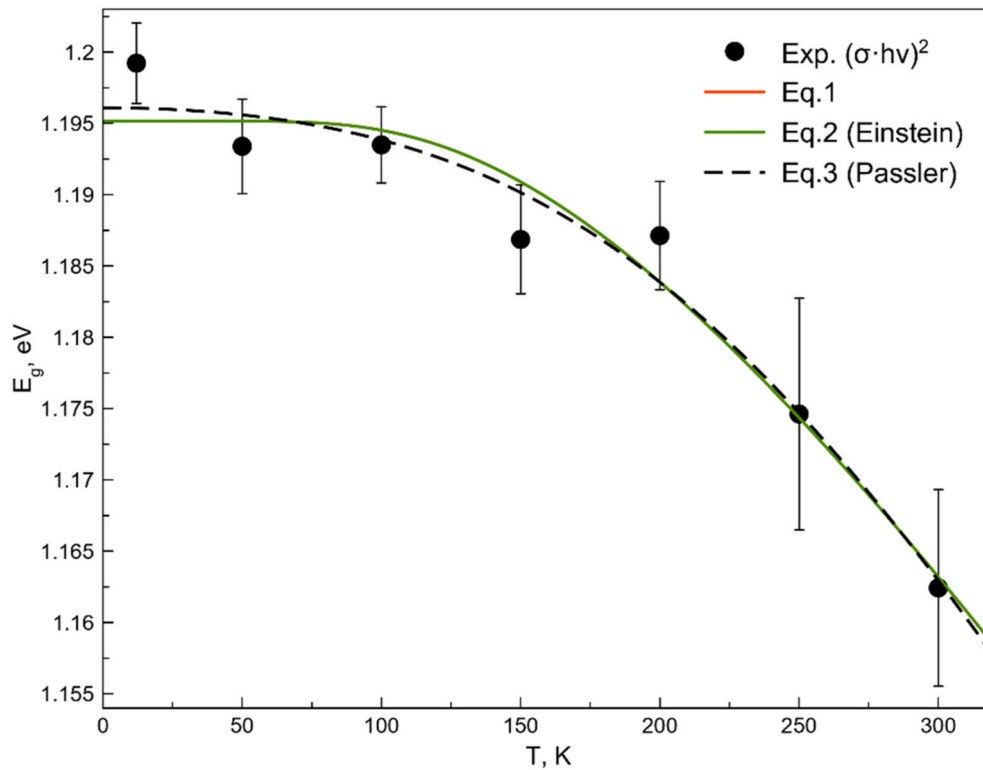


Fig. 2. Experimental band gap energy vs. temperature for Ca_2Si . Black dots – experimental data $(\sigma h\nu)^2$; lines – fitting based on models (1), (2) and (3).

PC signal of the $\text{Ca}_2\text{Si}/\text{Si}$ system is provided by Ca_2Si film.

The obscure point of the studied compound is whether it is possible to consider epitaxial films of Ca_2Si as direct or indirect gap semiconductor with a band gap of about 1.0 eV according to *ab-initio* quasiparticle calculations [4] and experimental study [17].

The fundamental absorption edge in a semiconductor is proportional to the absorption coefficient [23], and the type of fundamental transition determines the dependence of the absorption coefficient on the photon energy ($h\nu$), which specifies band gap type - direct or indirect. It is then possible to determine the band gap [24] and its temperature dependence from the PC spectrum measured in a wide temperature range. Assuming a direct band gap the band gap energies of the Ca_2Si semiconductor were estimated by extrapolating the linear portion of PC graphs of $(\sigma h\nu)^2$ versus $h\nu$ to zero [24] (Fig. 2 – black dots). Following Ref. [25] the temperature dependence of the direct gap was studied using three different models, the three-parameter thermodynamic model of O'Donnell and Chen [20], the Einstein model [21] and the Pässler model [22].

Firstly, O'Donnell and Chen stated that the temperature-dependent electron-phonon interactions effectively determine semiconductor bandgaps. The band gap reflects the bond energy. An increase in temperature changes the chemical bonding as electrons are promoted from the valence band to the conduction band [20]. The electron-phonon interaction, in this case, is dominant and can be described by a three-parameter thermodynamic model:

$$E_g(T) = E_g(0) - S \cdot E_{ph} \left[\coth\left(\frac{E_{ph}}{2kT}\right) - 1 \right], \quad (1)$$

where $E_g(0)$ is the bandgap at $T = 0$ K, E_{ph} is effective phonon energy, and S is a dimensionless constant related to the electron-phonon coupling. This thermodynamic model provides a good description of $E_g(T)$ for various semiconducting materials [25].

Second, in the Einstein model, the $E_g(T)$ dependence can be expressed by the following equation [21]:

Table 1

Parameters calculated using models (1), (2), and (3) that approximate band gap temperature relation from PC of Ca_2Si .

	Parameters	
Eq. (1)	$E_g(0)$, eV	1.195 ± 0.002
	$\langle E_{ph} \rangle$, meV	48.3 ± 1.8
	S	1.819 ± 0.17
Eq. (2) (Einstein model)	$E_g(0)$, eV	1.195 ± 0.002
	K , eV	0.175 ± 0.14
	Ξ , K	561 ± 212
Eq. (3) (Pässler model)	$E_g(0)$, eV	1.196 ± 0.002
	α , meV K ⁻¹	14.21 ± 5.87
	θ , K	2734 ± 854
	r	0.048 ± 0.022

$$E_g(T) = E_g(0) - K(e^{\frac{T}{\Xi}} - 1)^{-1}, \quad (2)$$

where K is a temperature-independent constant and Ξ is the Einstein temperature.

Thirdly, eq. (3) provides a good approximation of the analytical description of $E_g(T)$ proposed by Pässler [22], in the case when electron-phonon interaction is dominant. It is worth mentioning that this form of the Pässler equation represents a reasonable approximation for $r > 0.15$.

$$E_g(T) = E_g(0) - \alpha \left(\frac{\theta}{2}\right) \left[\left(1 + 2r \left(\frac{2T}{\theta}\right)^2 + \left(\frac{2T}{\theta}\right)^4 \right)^{\frac{1}{4}} - 1 \right] \quad (3)$$

The temperature relation of experimental E_g , calculated from extrapolation of PC curves, and the fitting plots of the three-parameter thermodynamic model, the Einstein model and the Pässler model are given in Fig. 2. The fitting plots of all models predict experimental results reasonably well. For all models, the coefficient of determination,

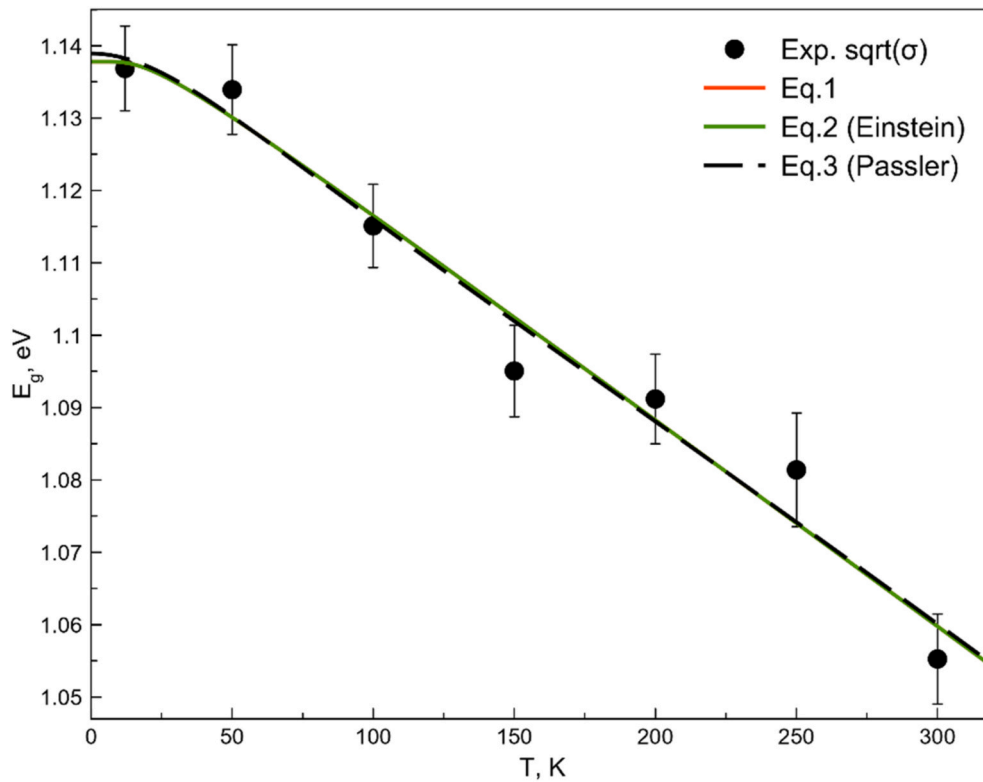


Fig. 3. Experimental band gap energy vs. temperature for Ca₂Si calculated in $\sqrt{\sigma}$ coordinates. Black dots — experimental data, solid lines — fitting based on models (1), (2), and (3).

which ascertains the fitting accuracy, is greater than 0.9750. The obtained fitting parameters are summarised in Table I.

By fitting experimental data to eq. (1) and eq. (2) the following set of parameters were obtained: $E_g(0) = 1.195$ eV, $\langle E_{ph} \rangle = 48.3 \pm 1.8$ meV, $S = 1.819 \pm 0.17$, $K = 0.175$ and Einstein temperature 561 K. The latter are close to the Debye temperature reported for Si (600 K) [27] and silicides Mg₂Si (432 K) [28], CrSi₂ (793 K) [29] and FeSi₂ (640 K) [30]. The determined width of the direct band gap at room temperature (1.195 eV) agrees well with the of optical spectroscopy band gap data (1.095 eV) for Ca₂Si films grown by this technology [18].

Our value of the electron-phonon coupling parameter S is higher than the reported value for Si (1.49) [20,26] and lower than that for III–V compounds like InP (1.94) [21,31], GaAs (3.0) and GaP (3.35) [20,26]. It can be concluded that the interaction between band-edge states and the phonon system in Ca₂Si is stronger than in silicon and not so strong as in indium or gallium phosphides and arsenides [25].

Pässler’s model is not valid in our case. The value of r is much smaller than 0.15. From Eq. (1) or Eq. (2) we can write [26]:

$$\frac{dE_g}{dT} = - \frac{SE_{ph}^2}{2kT^2 \sinh^2(E_{ph}/2kT)} \quad (4)$$

At high temperatures, $k_B T \gg E_{ph}$ and the slope of the E_g vs T curve approaches its limiting value [26]:

$$- \left[\frac{dE_g}{dT} \right]_{max} = 2Sk_B \quad (5)$$

Comparing the above given $T \rightarrow \infty$ asymptote of Eq. (1) or Eq. (2) with its counterpart due to equation (2), the following correlations between the different model parameters are found:

$2Sk_B = K/\Xi = \delta$ for the magnitude of the limiting slope and $E_{ph}/k_B = \Xi = \Theta_D$ for the effective phonon temperature [25]. Comparing the parameter values listed in Table I, we conclude that, within deviations of less than 5%, these theoretical relations are fulfilled for the

Table 2

Parameters calculated using models (1), (2), and (3) that approximate band gap temperature relation from PC of Ca₂Si.

	Parameters	
Eq. (1)	$E_g(0)$, eV	1.137 ± 0.007
	$\langle E_{ph} \rangle$, meV	4.8 ± 7.6
	S	1.66 ± 0.23
Eq. (2) (Einstein model)	$E_g(0)$, eV	1.137 ± 0.007
	K , eV	0.016 ± 0.027
	Ξ , K	56 ± 88
Eq. (3) (Pässler model)	$E_g(0)$, eV	1.139 ± 0.008
	α , meV K ⁻¹	0.323 ± 0.067
	θ , K	247 ± 668
	r	3.58 ± 4.56

three-parameter thermodynamic model and the Einstein model, and not for the Pässler model.

Assuming that mobility μ is determined by lattice scattering, its value can be expressed by [25,32].

$$\mu = \frac{48}{9\pi} \left[\frac{3}{4\pi} \right]^{1/3} \left[\frac{\pi}{2} \right]^{1/2} \frac{e\hbar^2 k}{(\Omega)^{1/3} m^{*3/2} (kT)^{3/2} \partial E_g / \partial T}, \quad (6)$$

where Ω is the volume of the unit cell and m^* is the effective mass. The hole mobility was calculated by assuming that the hole effective mass $m_h/m_0 = 1.0$. At room temperature, we estimate hole mobility of $\mu = 98$ cm²/Vs (by applying the thermodynamic model and the Einstein model). The value is lower than that reported for the room temperature effective Hall mobility value [17].

The band gap energies of Ca₂Si were also estimated by extrapolating the linear portion of PC graphs of $\sqrt{\sigma}$ versus $h\nu$ to zero [24] assuming that Ca₂Si could be possible indirect gap material. Fig. 3 shows such a

relation of E_g with temperature. Similar to the previous case, three different models were used to approximate the temperature relation of the band gap. The obtained fitting parameters are given in Table II.

Both, the thermodynamic and the Einstein model very underestimate the effective phonon energy and Einstein temperature. As far as Pässler model is concerned by fitting equation (3) to our data of $E_g(T)$, the following set of parameters is obtained: $E_g(0) = 1.139$ eV, $\theta = 247$ K, $r = 3.58$, and $\alpha = 0.323$ meV K⁻¹ (Table II). However, the Pässler model restrictive requirement namely r lower than $\pi^2/12$ is not valid for the case of our Ca₂Si data. It means that the model could not be applied to Ca₂Si $E_g(T)$ data.

We can conclude that both the three-parameter models are good enough to fit the experimental $E_g(T)$ data within the accuracy of the measurement assuming that Ca₂Si is direct gap material. The four-parameter Pässler model is not valid in our case. Analysis of $E_g(T)$ was done in assuming that Ca₂Si is an indirect or direct gap compound. The latter shows reasonable results in contrast to that of the former one. It can be considered as ancillary confirmation of the direct gap nature of Ca₂Si.

4. Conclusions

The photoconductive measurements of Ca₂Si/Si system have been carried out. The temperature dependence of the direct band gap in Ca₂Si film in the temperature range of 12–300 K, was studied by using a three-parameter thermodynamic model, the Einstein model and the Pässler model. The first two models showed reasonably good fits to experimental data on temperature variation of the band gap in the case of the Ca₂Si direct gap approach. The values of the band gap at $T = 0$ K, a dimensionless constant related to the electron-phonon coupling and an estimation for the room-temperature hole mobility of Ca₂Si, have been derived from the applied models. The latter are within the experimental accuracy of the data, and show a good overlap between estimated data from the fitting parameters and experimental data and data in the literature.

CRedit authorship contribution statement

Nikita Siminel: Writing – original draft, Software, Investigation, Formal analysis. **Konstantin N. Galkin:** Writing – review & editing, Formal analysis, Conceptualization. **Ernest Arushanov:** Writing – review & editing, Supervision, Project administration, Methodology, Data curation, Conceptualization. **Nikolay G. Galkin:** Writing – review & editing, Methodology, Investigation, Funding acquisition, Data curation, Conceptualization.

Declaration of competing interest

The authors declare that they have no known competing financial interests or personal relationships that could have appeared to influence the work reported in this paper.

Data availability

Data will be made available on request.

Acknowledgments

This work was carried out with financial support from the Russian Foundation for Basic Research grant (No. 20-52-00001-Be1_a). The authors thank PhD E.A. Chusovitin and young researcher E. Yu. Subbotin for preparing the test integrated structure and ultrasonic compression of Al contacts to the Ca₂Si film for low-temperature measurements of conductivity and photoconductivity and Dr. Sci. D.L. Goroshko - for fruitful discussions.

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